In the Claims:

Please cancel claim 8 without prejudice.

Please amend claims 9, 10, 11, 12, and 13 as follows:

Claims 1-8. (canceled)

9. (currently amended) A method for producing the redundantly constrained laminar structures as weak-link mechanisms ~~as recited in claim 8 further includes the steps of~~ by lithographic techniques comprising the steps of:

repeatedly chemically etching a designed pattern with a mask to produce a plurality of individual substantially identical units;

stacking the units together to form the laminar structure;

securing the stacked units together with fasteners received in predefined locating-holes in said units; and applying an adhesive to the sides of the laminar structure to provide the mechanism equivalent to a single piece mechanism.

10. (currently amended) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim ~~8~~ 9 wherein each of said plurality of individual substantially identical units is formed of a ~~thin~~ selected sheet material.

11. (currently amended) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim ~~8~~ 9 wherein each of said plurality of individual substantially identical units is formed of a ~~thin~~ metal material.

12. (currently amended) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim ~~8~~ 9 wherein the step of repeatedly chemically etching a designed pattern with a mask to produce a plurality of individual substantially identical units includes the step of repeatedly chemically etching a designed pattern having multiple weak-link connections with a mask to produce a plurality of individual substantially identical units.

13. (currently amended) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim ~~8~~ 9 wherein the step of repeatedly chemically etching a designed pattern with a mask to produce a plurality of individual substantially identical units includes the step of repeatedly chemically etching a designed pattern with a mask to produce a set number of individual substantially identical units.

14. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim 13 wherein said set number of individual substantially identical units is selected for providing a predefined stiffness for the laminar structure.